THIN FILM MATERIALS · TECHNICAL PLANNING REFERENCE

AZO Sputtering Target

Typical Specification Sheet · For preliminary RFQ discussion

Planning reference only. Illustrative values are not a batch CoA or guaranteed acceptance limits; order-specific requirements and actual batch documentation govern.

AZO	99.9900%	100 ppm	PASS
Material	Illustrative matrix	Illustrative impurities	Closed arithmetic

Reference product definition

Reference grade	97/3 wt% ZnO/Al2O3; 4N oxide-basis planning grade
Order-specific scope	Geometry, finished dimensions, tolerances, bonding/backing, inspection and acceptance criteria are per approved drawing and quotation.

Closed illustrative composition model

The nominal 97:3 oxide ratio is proportionally scaled to a 99.9900 wt% matrix so the illustrative impurities can be included in a closed 100.0000 wt% model. Basis: wt%, total mass basis.

Constituent	Illustrative wt%	Equivalent ppm	Role
ZnO	**96.9903**	—	nominal 97-part oxide
Al2O3	**2.9997**	—	nominal 3-part oxide
Fe	0.0010	10	illustrative typical impurity
Si	0.0010	10	illustrative typical impurity
Cu	0.0010	10	illustrative typical impurity
Pb	0.0010	10	illustrative typical impurity
Ni	0.0010	10	illustrative typical impurity
Na	0.0010	10	illustrative typical impurity
Other	0.0040	40	illustrative typical impurity
Total impurities	**0.0100**	**100**	**arithmetic checked**
COMPOSITION TOTAL	**100.0000**	—	**PASS**

ARITHMETIC VALIDATION: matrix 99.9900 wt% + illustrative impurities 0.0100 wt% = 100.0000 wt%. Individual impurity sum = 100 ppm. ALL CHECKS PASS.

Information to include in an RFQ

Target geometry and drawing/revision · finished dimensions and tolerances · required purity/composition basis · controlled impurities · planar or rotary configuration · bonding/backing requirement · quantity · inspection and document requirements.

Use this sheet only for early engineering discussion. Request an order-specific specification and the actual batch CoA before material acceptance or use.